

Combined texture-structure-microstructure-phase analysis of multi-phased bulks and thin films using x-ray and neutron diffraction: some case studies, Bi2223, Ca₃Co₄O₉, PCT and nano-Si.

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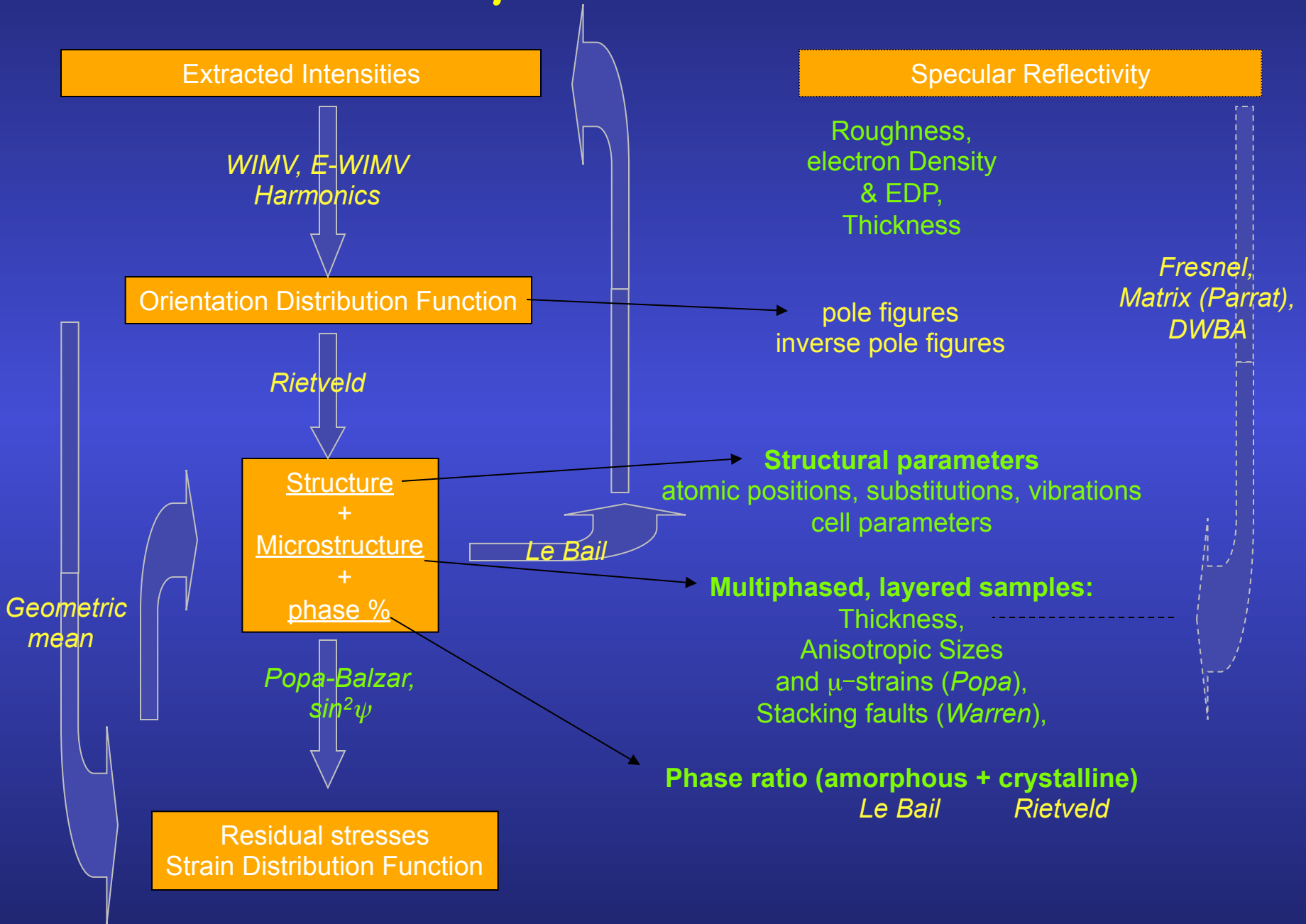
Bi2223
Superconductors

Ca₃Co₄O₉
Thermoelectrics

PCT
Ferroelectrics

Nano-Si
thin films

Implemented codes



Extracted Intensities

*WIMV, E-WIMV
Harmonics*

Orientation Distribution Function

Rietveld

Structure
+
Microstructure
+
phase %

*Popa-Balzar,
 $\sin^2\psi$*

Residual stresses
Strain Distribution Function

Specular Reflectivity

Roughness,
electron Density
& EDP,
Thickness

pole figures
inverse pole figures

Structural parameters
atomic positions, substitutions, vibrations
cell parameters

Multiphased, layered samples:
Thickness,
Anisotropic Sizes
and μ -strains (*Popa*),
Stacking faults (*Warren*),

Phase ratio (amorphous + crystalline)
Le Bail *Rietveld*

*Fresnel,
Matrix (Parrat),
DWBA*

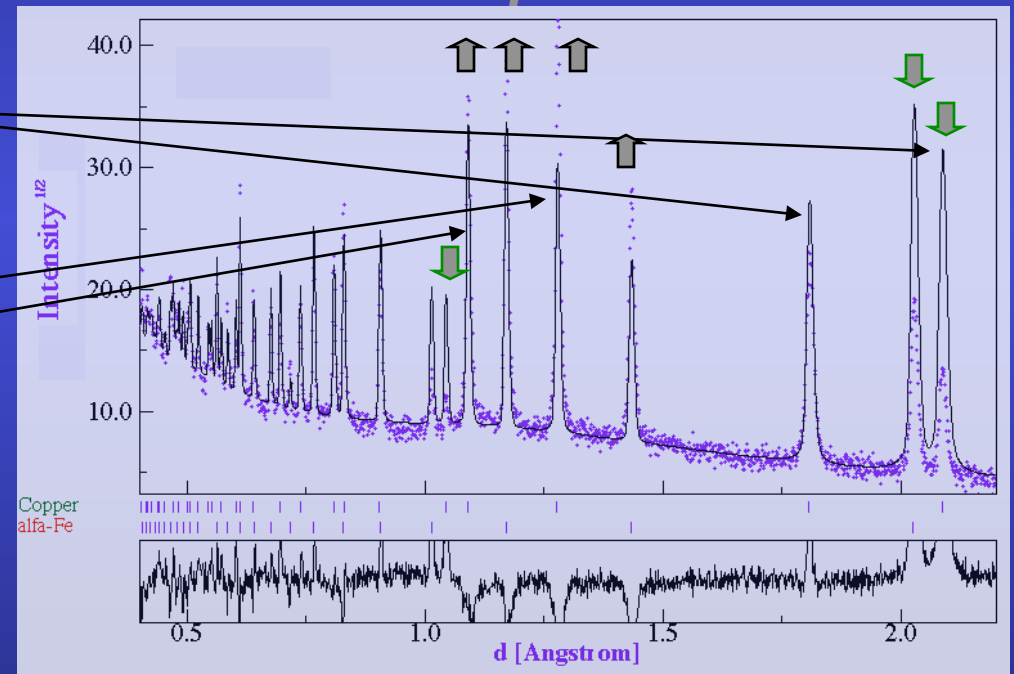
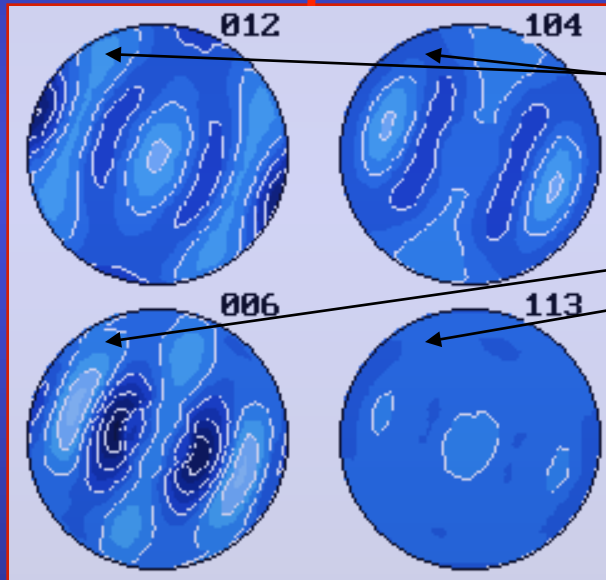
*Geometric
mean*

Texture from Spectra

Orientation Distribution Function (ODF)

From pole figures

From spectra



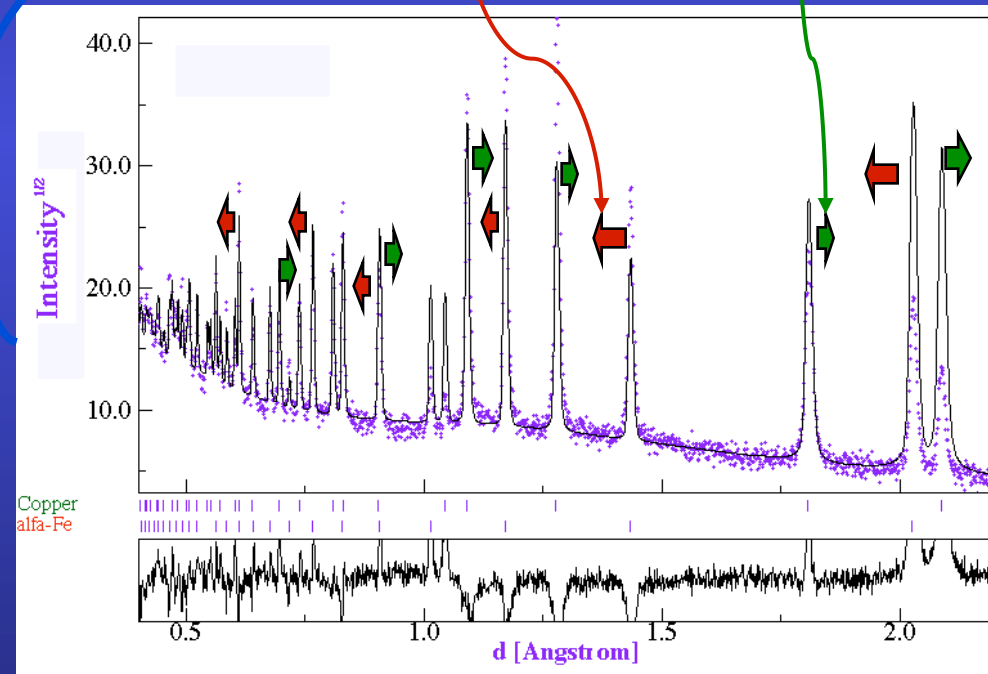
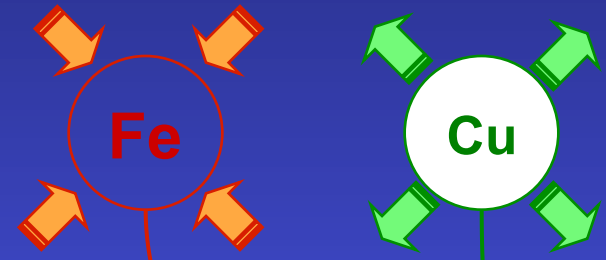
Residual Stresses and Rietveld

- Macro elastic strain tensor (I kind)
- Crystal anisotropic strains (II kind)

C

Macro and micro stresses

Applied macro stresses



Textured samples: Reuss, Voigt, Hill, Bulk geometric mean approaches

How it works (Combined)

$$I_i^{calc}(\chi, \phi) = \sum_{n=1}^{Nphases} S_n \sum_k L_k |F_{k;n}|^2 S(2\theta_i - 2\theta_{k;n}) P_{k;n}(\chi, \phi) A + bkg_i$$

Texture

$$P_k(\chi, \phi) = \int_{\varphi} f(g, \varphi) d\varphi$$

- from Generalized Spherical Harmonics:

$$P_k(\chi, \phi) = \sum_{l=0}^{\infty} \frac{1}{2l+1} \sum_{n=-l}^l k_l^n(\chi, \phi) \sum_{m=-l}^l C_l^{mn} k_n^{*m}(\Theta_k \phi_k)$$

$$f(g) = \sum_{l=0}^{\infty} \sum_{m,n=-l}^l C_l^{mn} T_l^{mn}(g)$$

- from the WIMV iterative process:

$$f^{n+1}(g) = N \left[\frac{f^n(g) f^0(g)}{\prod_{hkl} (P_{hkl}^n(\vec{y}))^{\frac{1}{l}}} \right]$$

Layering

$$C_{\chi}^{\text{top film}} = g_1 (1 - \exp(-\mu T g_2 / \cos \chi)) / (1 - \exp(-2\mu T / \sin \omega \cos \chi))$$

$$C_{\chi}^{\text{cov. layer}} = C_{\chi}^{\text{top film}} \left(\exp(-g_2 \sum \mu'_i T'_i / \cos \chi) \right) / \left(\exp(-2 \sum \mu'_i T'_i / \sin \omega \cos \chi) \right)$$

DWBA

$$R(q_z) = \left| \frac{1}{\rho_{\infty}} \int_{-\infty}^{\infty} \frac{d\rho}{dz} e^{-iq_z z} dz \right|^2$$

Popa anisotropic shapes

$$\langle R_h \rangle = R_0 + R_1 P_2^0(x) + R_2 P_2^1(x) \cos \varphi + R_3 P_2^1(x) \sin \varphi + R_4 P_2^2(x) \cos 2\varphi + R_5 P_2^2(x) \sin 2\varphi +$$

...

Minimum experimental requirements

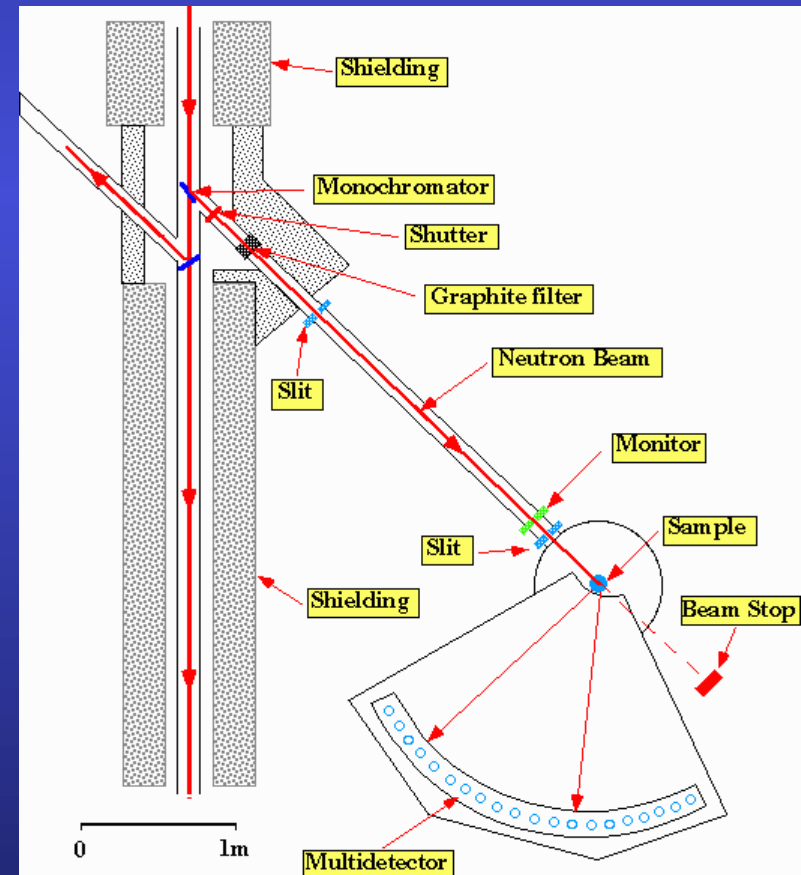
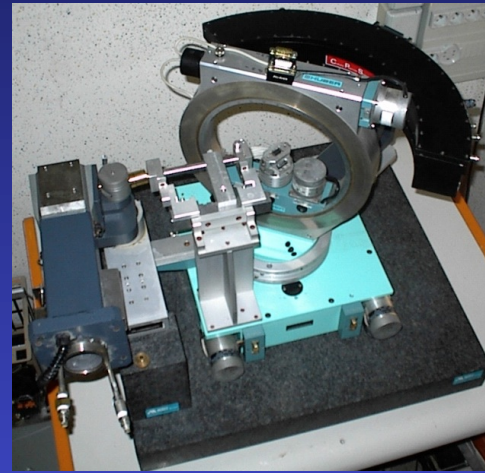
Curved Detector + 4-circle diffractometer
(X-rays and neutrons)
CRISMAT, ILL

+

~1000 experiments (2θ diagrams)
in as many sample orientations

+

Instrument calibration
(peaks widths and shapes,
misalignments, defocusing ...)



Methodology implementation

The screenshot shows the MAUD software interface. At the top, there's a 'TreeTable' window with a table of parameters:

Name	Value	Error	Status
_atom_site_aniso_U_12	0.0	0.0	Fixed
_atom_site_aniso_U_13	0.0	0.0	Fixed
_atom_site_aniso_U_22	0.0	0.0	Refined
_atom_site_aniso_U_23	0.0	0.0	Refined
_atom_site_aniso_U_33	0.0	0.0	Equal to
Copper			
_cell_length_a	3.614566...	0.00002	Refined

Below the table is the 'Refinement wizard' with several options:

- Background and scale parameters: Custom
- Previous + basic phase parameters: Custom
- Previous + microstructure parameters: Custom
- Previous + crystal structure parameters: Custom
- All parameters for texture: Custom

There are also 'Commands' buttons like 'Fix all parameters', 'Free all parameters', etc., and a 'Pole Figure plot' section with 'Reconstructed' and 'Experimental' options.

User friendly interface

This screenshot shows the MAUD software interface with a 'Microstructure' dialog box open. The dialog box has several sections:

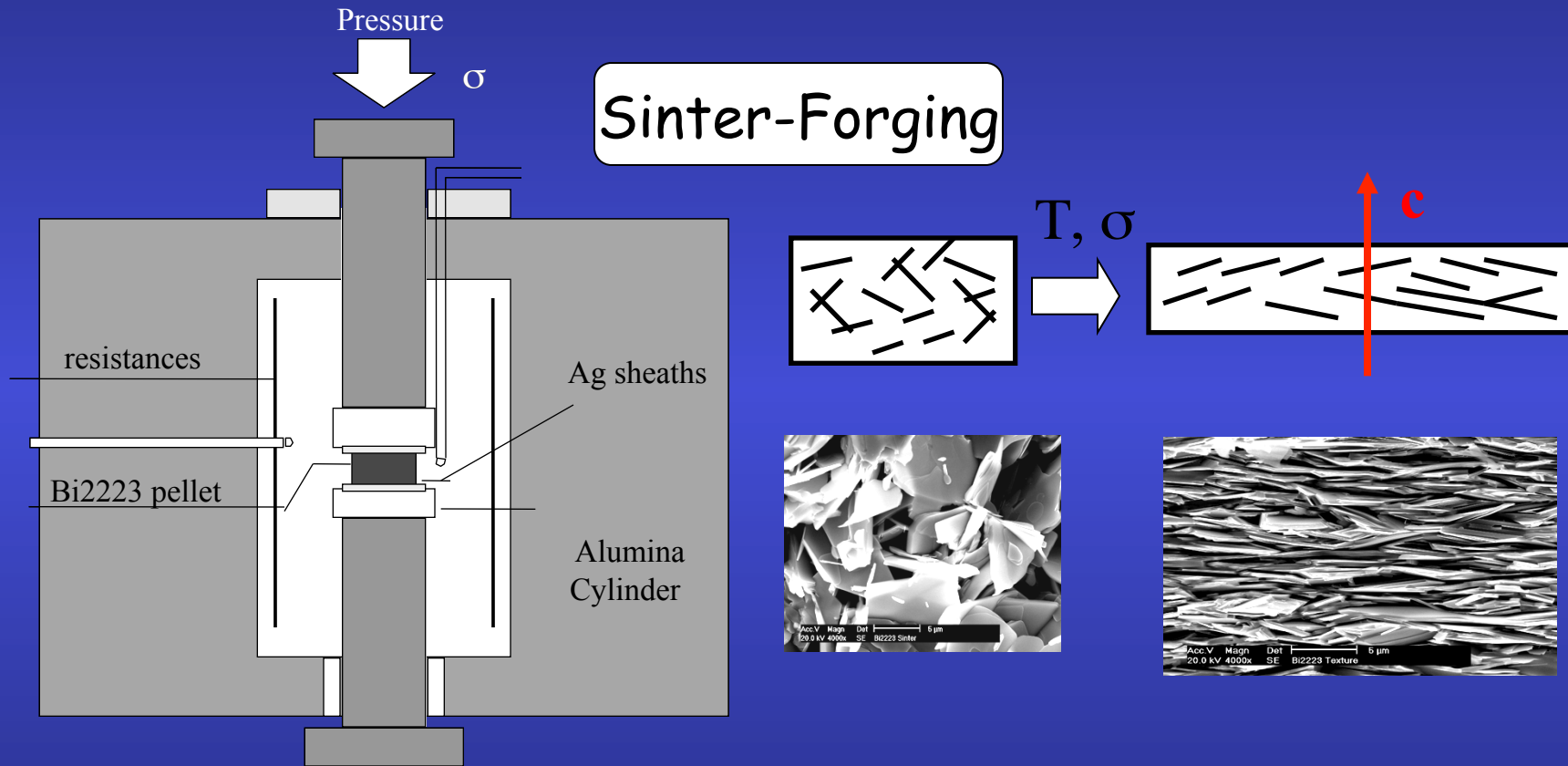
- Line Broadening:** Line Broadening model: Delf (selected), Options; Size-Strain model: Popa LB, Options; Antiphase boundary model: none abm, Options.
- Planar defects model:** none pd, Options.
- Microabsorption correction:** Grain size (microns): 5, Close, Cancel.

Below the dialog box, there's a 3D model of a yellow, irregularly shaped grain. At the bottom, there's a plot of intensity versus 2-Theta [degrees], showing a series of peaks. The x-axis ranges from 50.0 to 150.0 degrees.

Java codes
Java web start updates

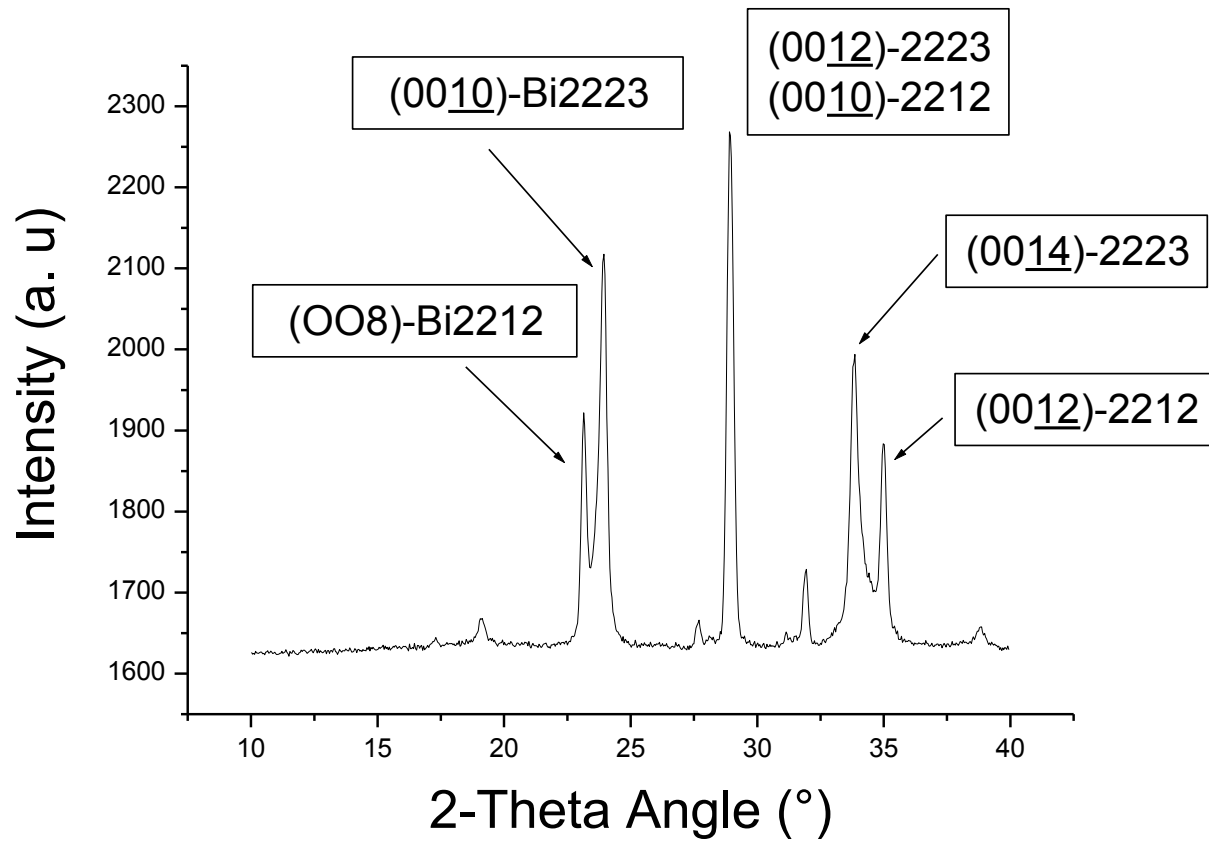
ation computation
or sample: CPD-Y203
ures: 14267.7133202
putation

Bi2223 compounds

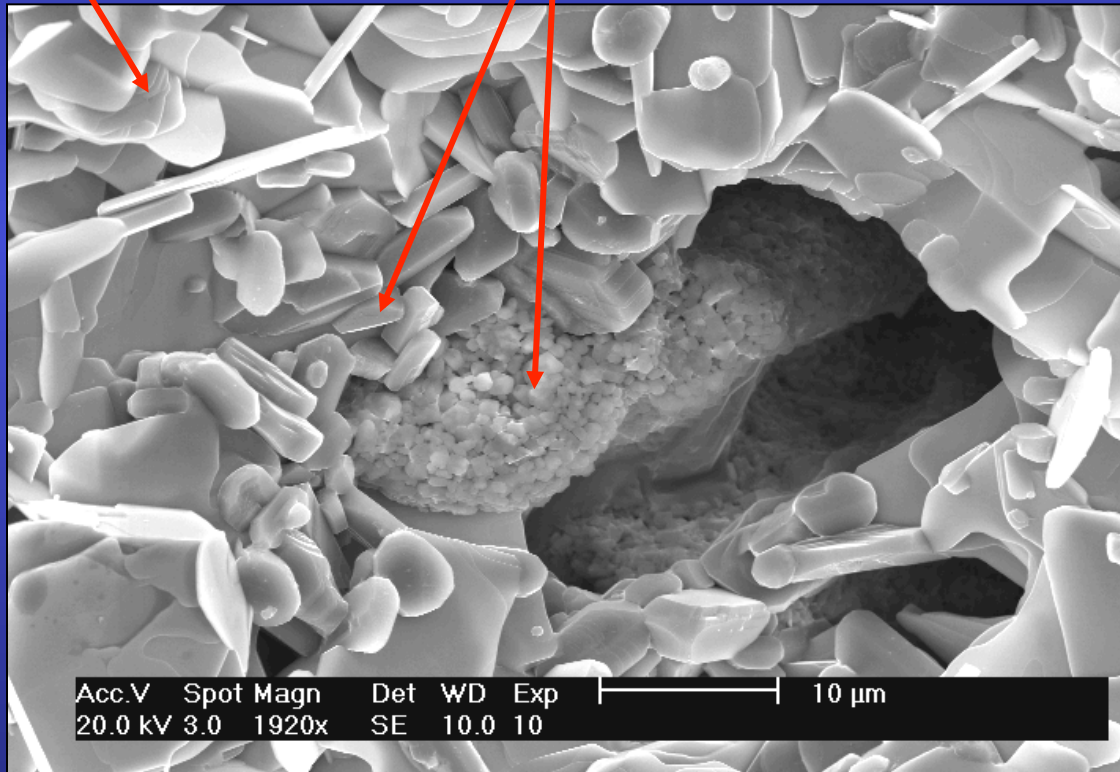


Grain alignment \Rightarrow \nearrow J_c

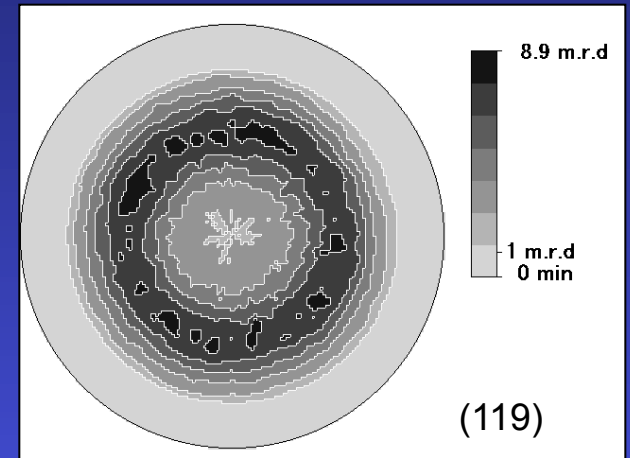
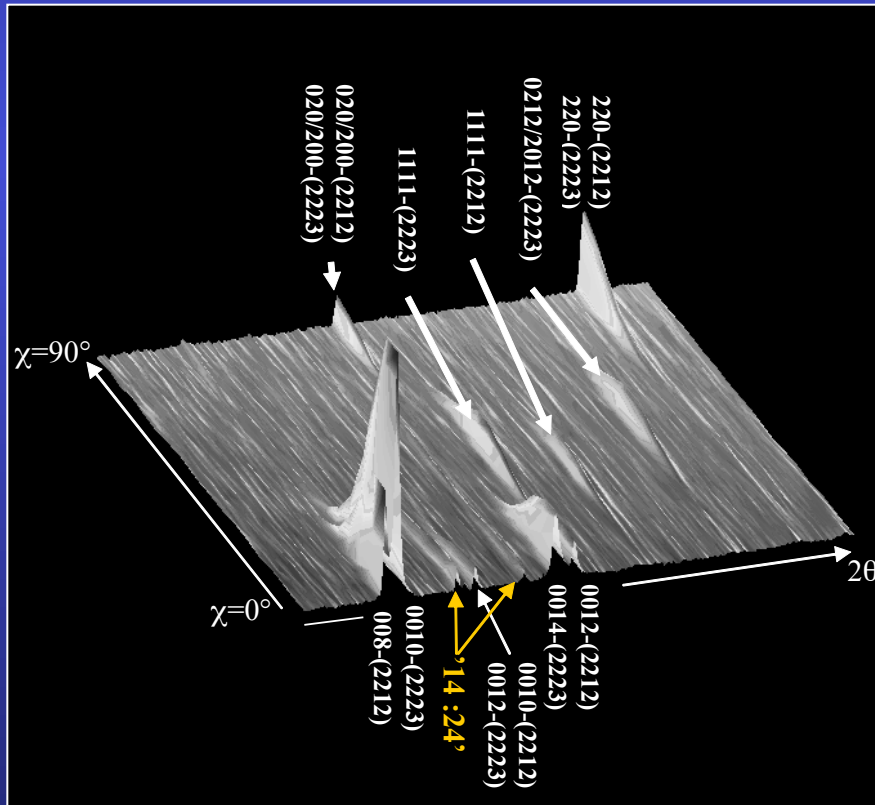
(00ℓ) Texture



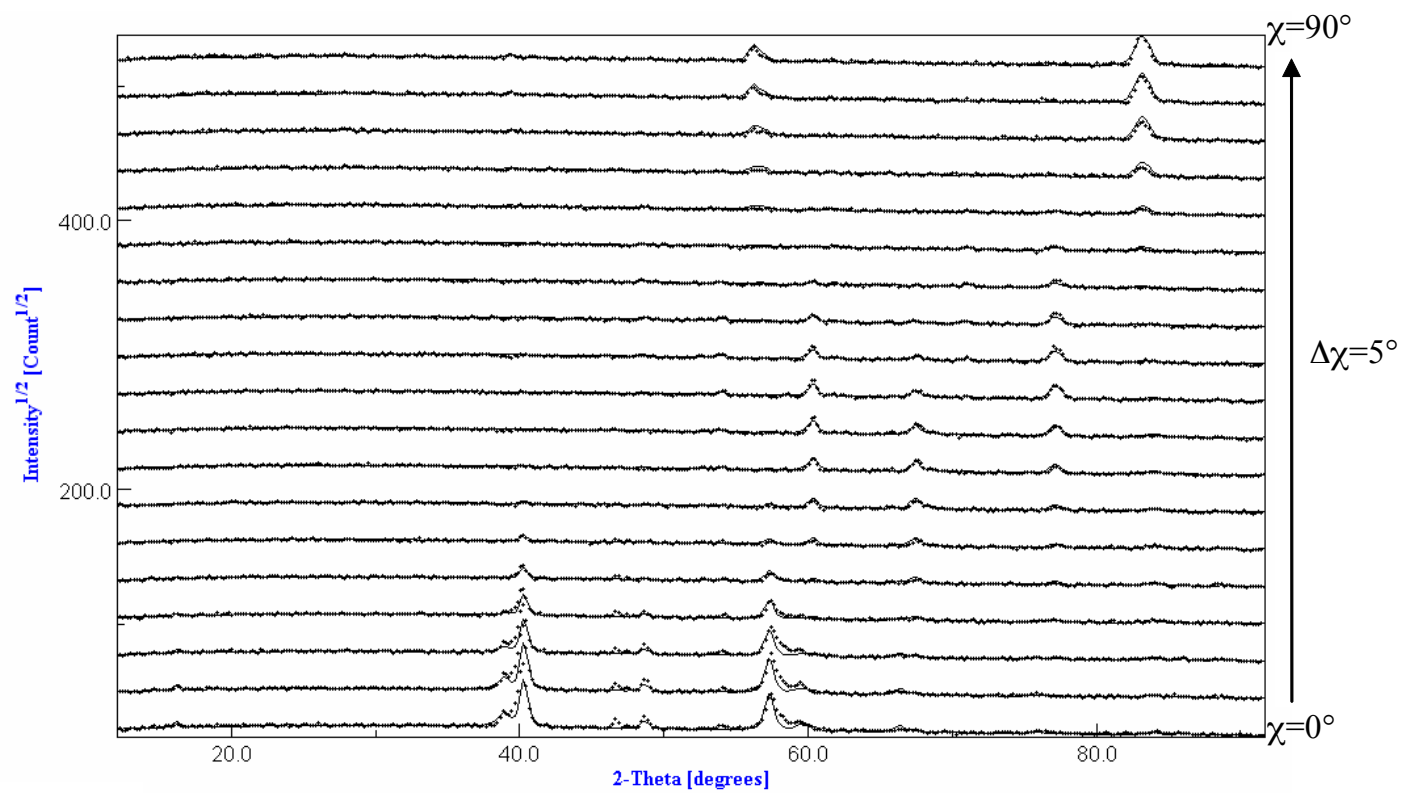
Bi2212 + Secondary phases \longrightarrow Bi2223



Combined Analysis



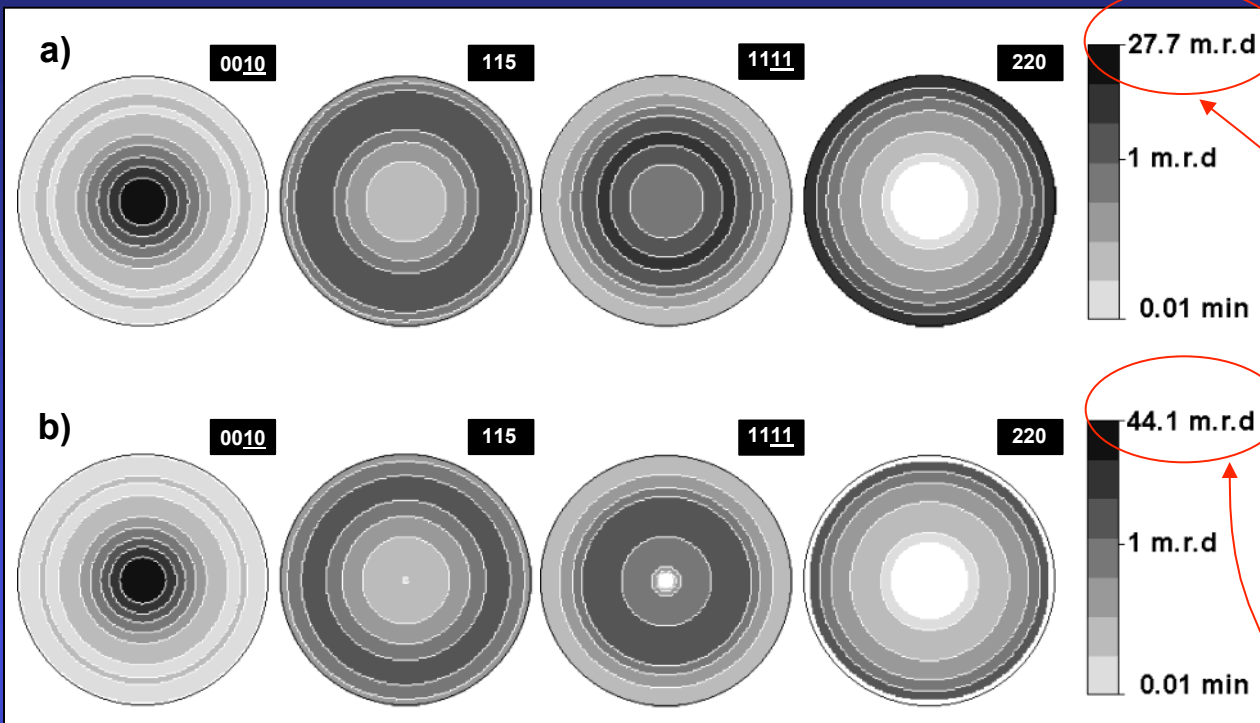
- Neutrons
- Sample: $\sim 70 \text{ mm}^3$
- 2θ patterns for $\chi=0^\circ$ to 90°
- No φ rotation (fibre texture).



2223
2212



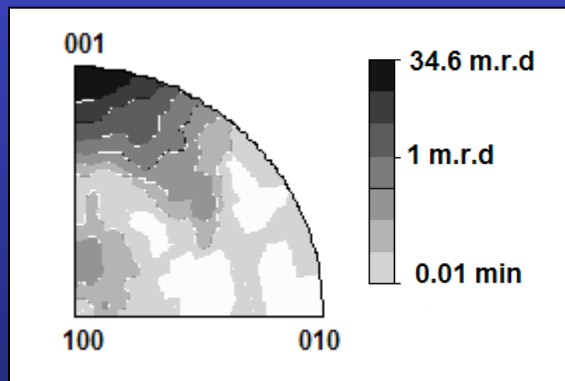
$R_w=9.12$
 $RP=16.24$



Logarithmic density scale, equal area projection

*Recalculated
(WIMV)*

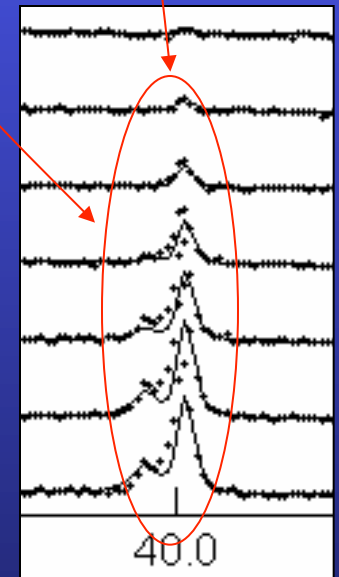
*Extracted
(Le Bail)*



Logarithmic density scale, equal area projection

Stacking faults and/or intergrowth on the c-axis
 → New periodicities and peaks characterized with intermediate c parameters.

However, no algorithm is included to solve intergrowths in the combined approach.



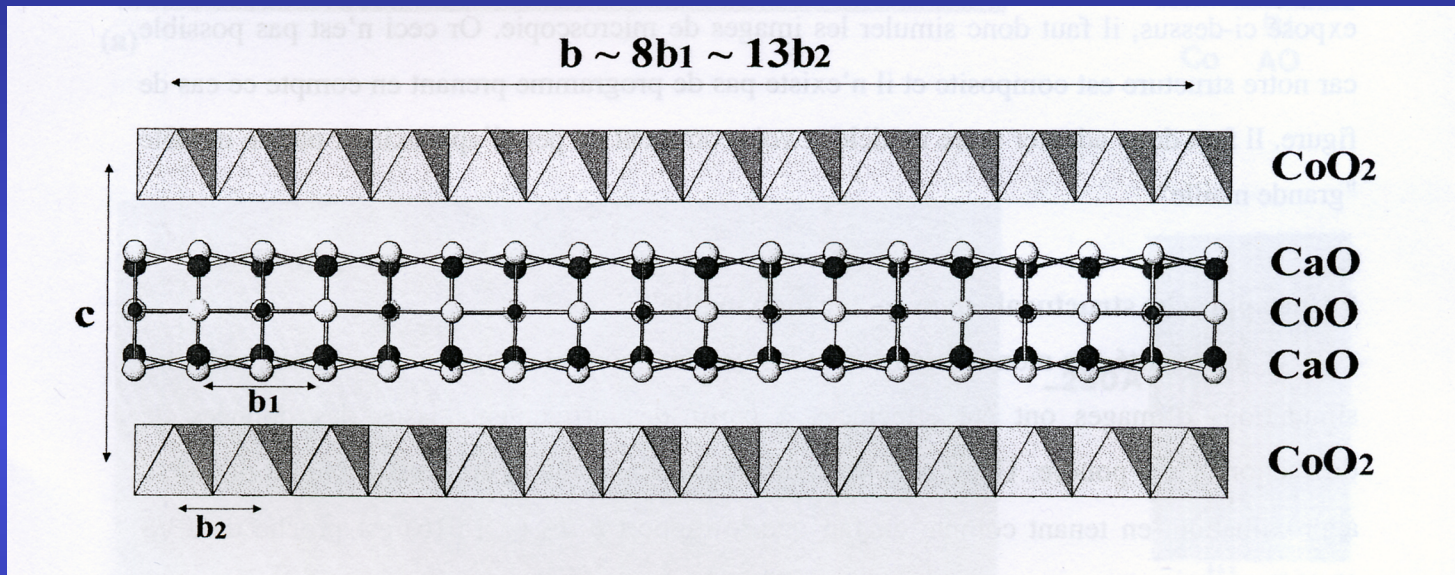
Effect of the sinter-forging treatment on the texture development, crystal growth, transport properties

Sinter-forging dwell time (h)	Orientation Distribution Max (m.r.d.)		% Bi2223	Cell parameters (Å)		Crystallite size Bi2223 (nm)	Rb (%)	Rw (%)	Rexp (%)	RP0 (%)	RP1 (%)	J_c (A/cm ²)
	Bi2212	Bi2223		Bi2223	Bi2212							
20	21.8	20.7	59.9±1.3	a=5.419(3) b=5.391(3) c=37.168(3)	a=5.414(3) b=5.393(3) c=30.800(3)	205±7	7.56	11.1	4.55	17.74	10.56	12500
50	24.1	24.4	72.9±2.9	a=5.419(3) b=5.408(3) c=37.192(3)	a=5.416(3) b=5.396(3) c=30.806(3)	273±10	7.54	11.37	4.58	17.05	11.04	15000
100	31.5	25.2	84.4±4.6	a=5.410(3) b=5.405(3) c=37.144(3)	a=5.412(3) b=5.403(3) c=30.752(3)	303±10	5.4	8.04	3.69	13.54	9.31	19000
150	65.4	27.2	87.0±4.1	a=5.417(3) b=5.403(3) c=37.199(3)	a=5.413(3) b=5.407(3) c=30.792(3)	383±13	6.13	9.12	4.8	16.24	12.25	20000



Ca₃Co₄O₉ thermoelectrics

Ca₃Co₄O₉: Misfit lamellar and modulated Structure, with high thermopower



Two monoclinic sub-systems:

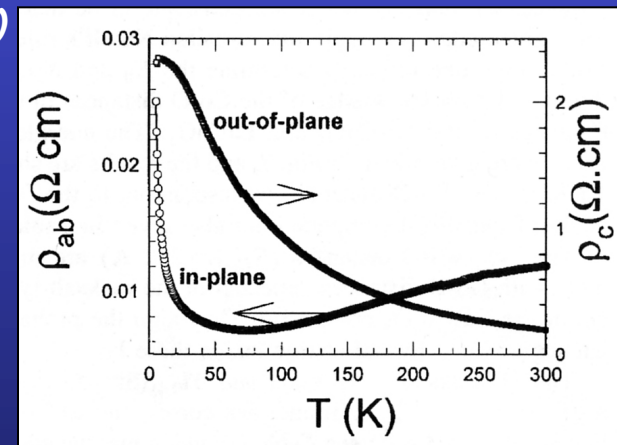
S1 with $a \sim 4.8\text{\AA}$, $b_1 \sim 4.5\text{\AA}$, $c \sim 10.8\text{\AA}$ et $\beta \sim 98^\circ$ (NaCl-type)

S2 with $a \sim 4.8\text{\AA}$, $b_2 \sim 2.8\text{\AA}$, $c \sim 10.8\text{\AA}$ et $\beta \sim 98^\circ$ (CdI₂-type)

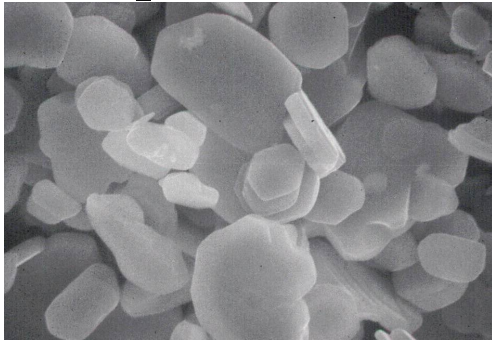
$$\Gamma = \sigma_{ab} / \sigma_c \sim 10$$



Texture

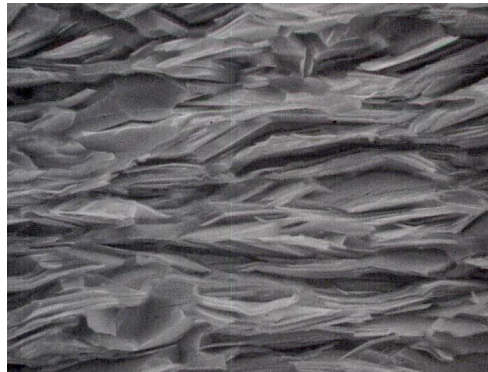


powder



10 μm

Textured bulk

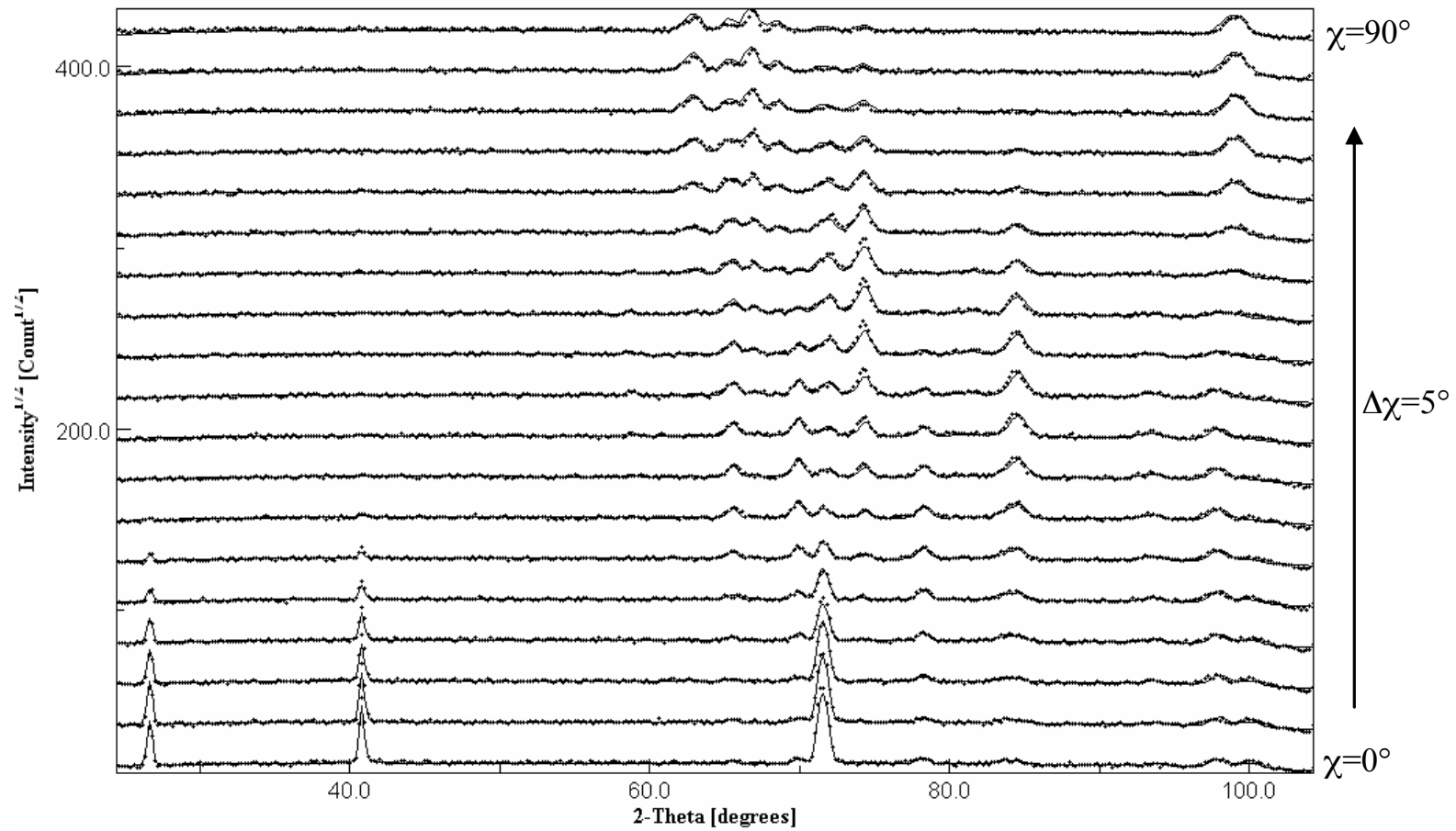


10 μm

*Magnetic alignment
and
Templated Growth
method*

Analysis:

- neutrons
- 3D Supercell: $a=4.8309\text{\AA}$, $b\sim 8b1\sim 13b2\sim 36.4902\text{\AA}$, $c=10.8353\text{\AA}$, $\beta=98.13^\circ$
174 atoms/cell
- Sample : 0.6 cm^3

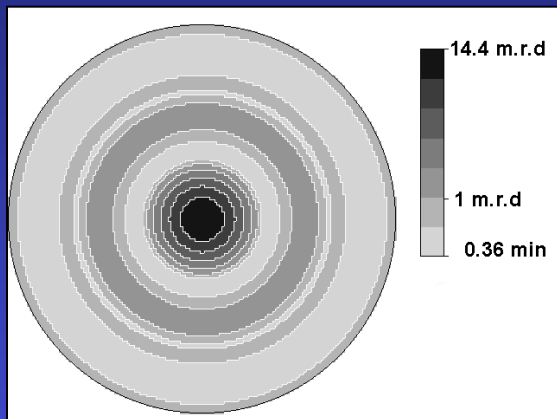


Supercell

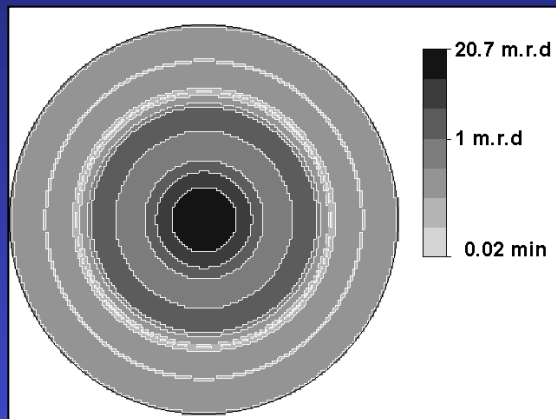


RP=19.7%, Rw=11.9%

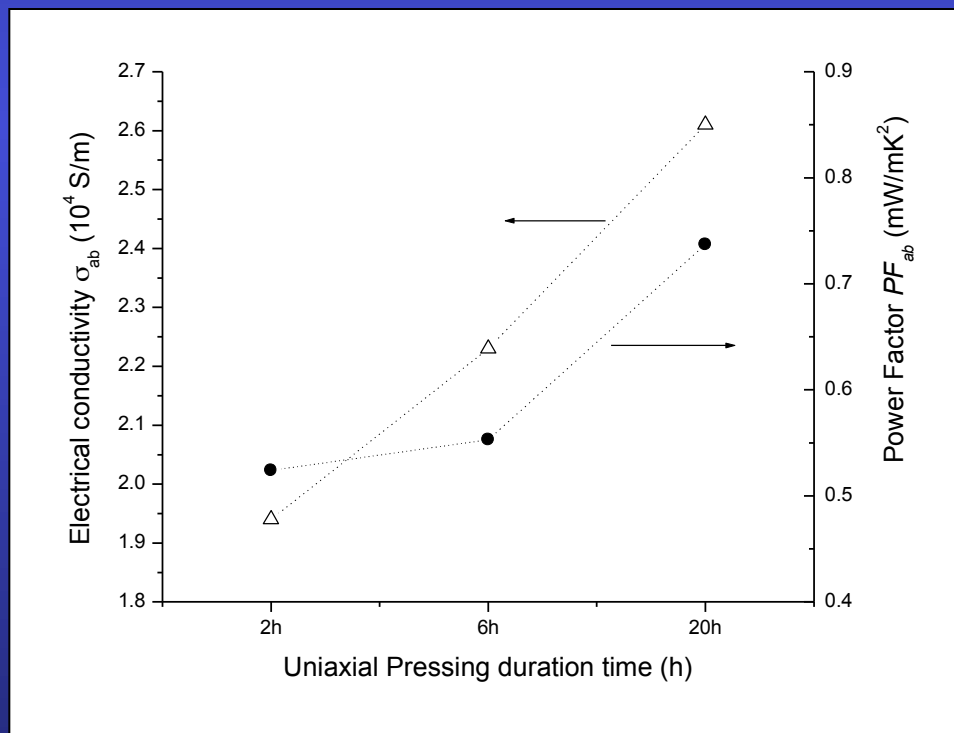
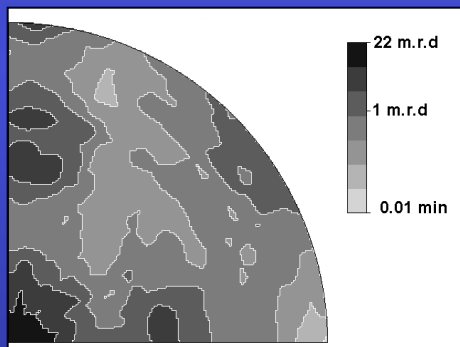
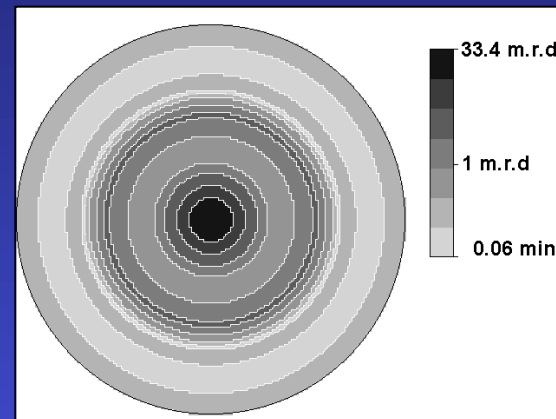
9.8 MPa for 2 h



19.6 MPa for 6 h

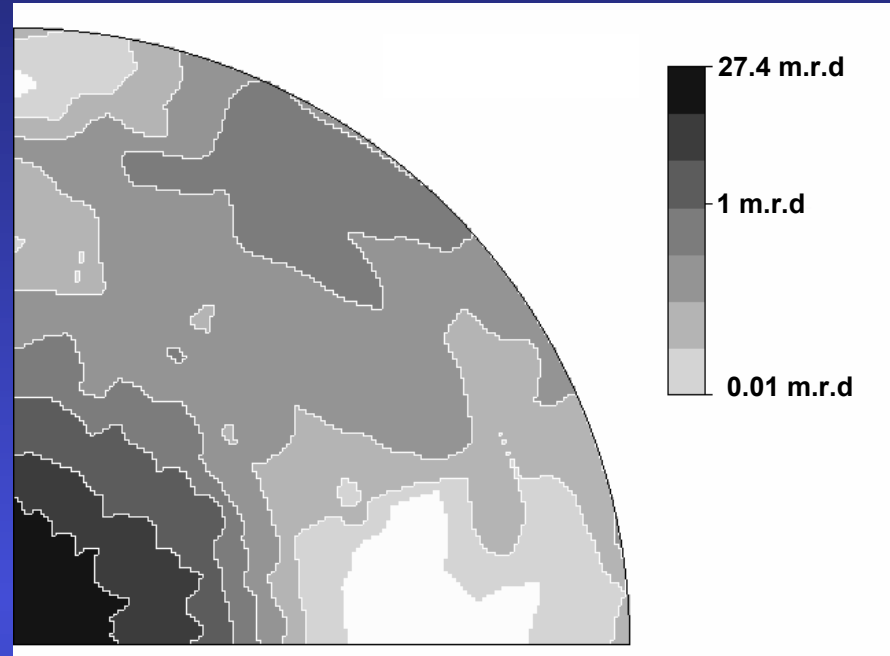


19.6 MPa for 20 h



Templated Growth Method

Logarithmic density scale, equal area projection



Magnetic Alignment



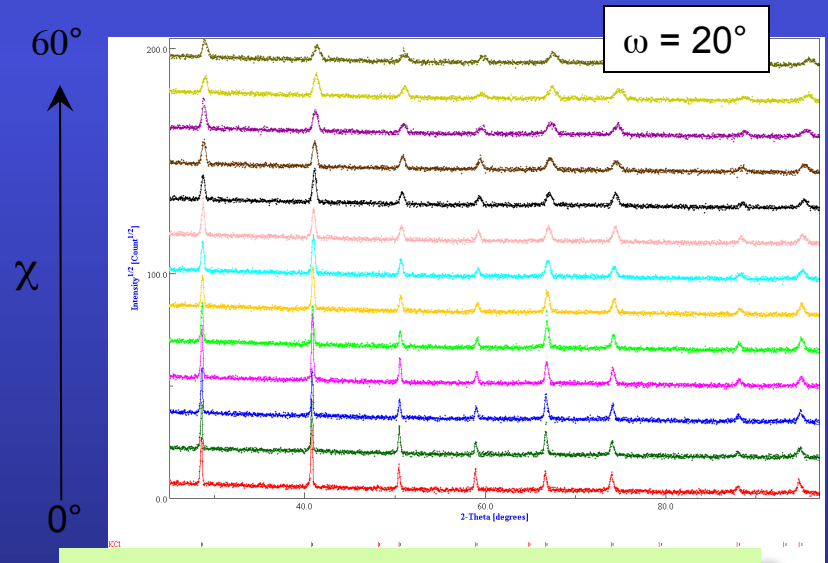
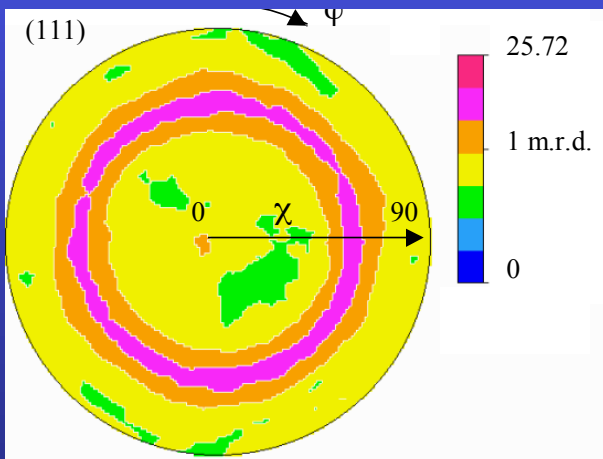
- *magnetic alignment really efficient to obtain strong textures*
- *combined analysis of modulated structures possible*

Ferroelectric PCT films

thin films:

$(\text{Ca}_{0.24}\text{Pb}_{0.76})\text{TiO}_3$ sol-gel synthesised solutions deposited by spin coating on a substrate of $\text{Pt}/\text{TiO}_2/\text{Si}$, with and without a treatment at 650°C for 30 min.

All films are crystallised at 700°C for 50 s by Rapid Thermal Processing (RTP; $30^\circ\text{C}/\text{s}$). A series is also recrystallised at 650°C for 1 to 3 h.



Refinement of individual spectra

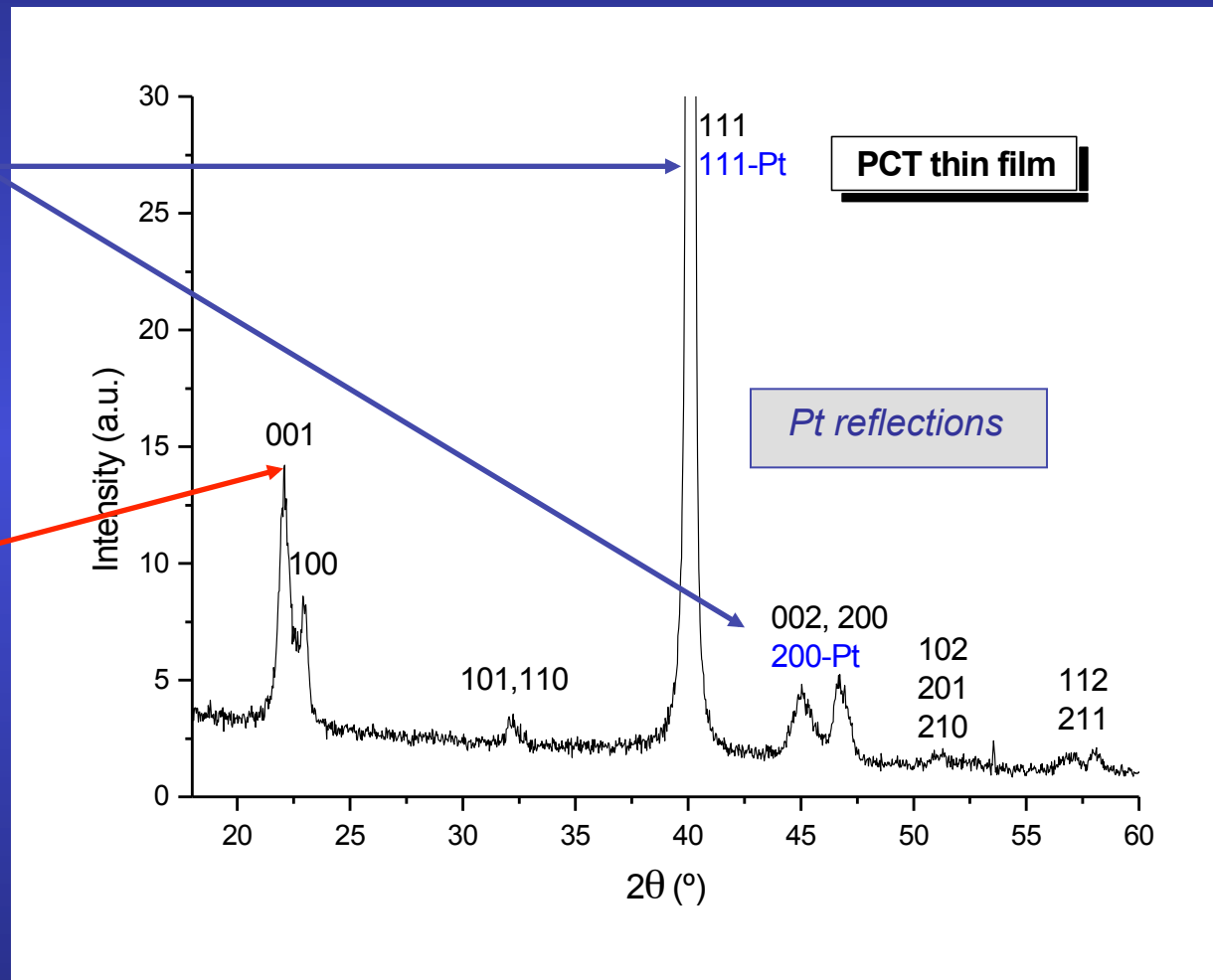
Limitations of the simple Quantitative Texture Analysis

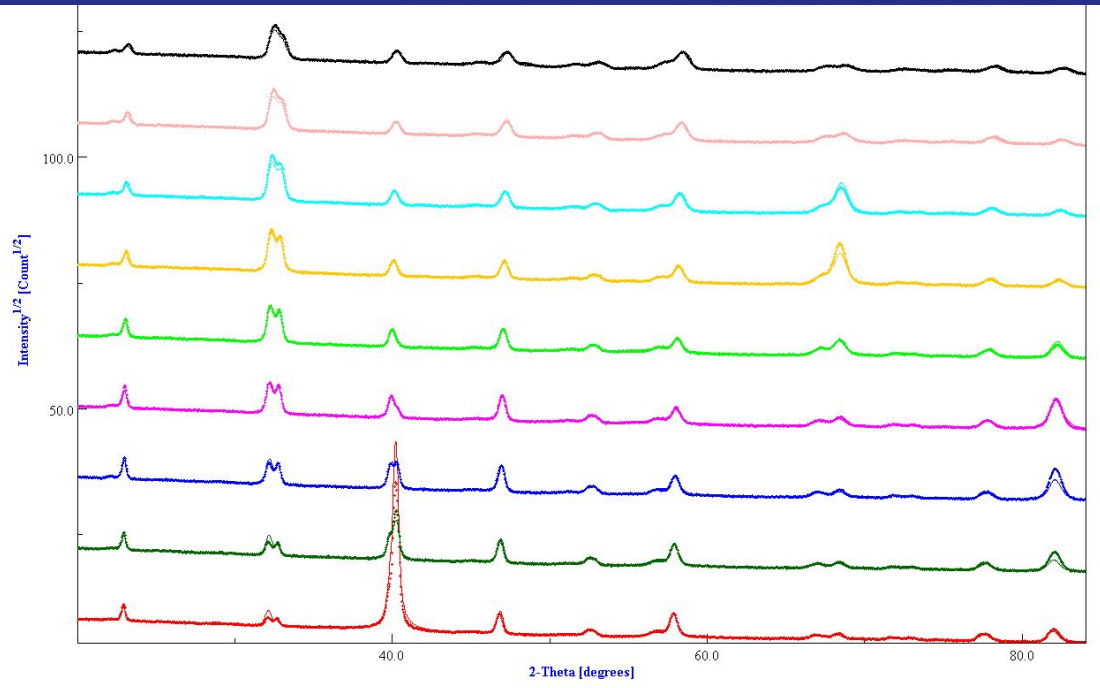
Structural parameters are difficult to obtain due to:

Substrate influence:

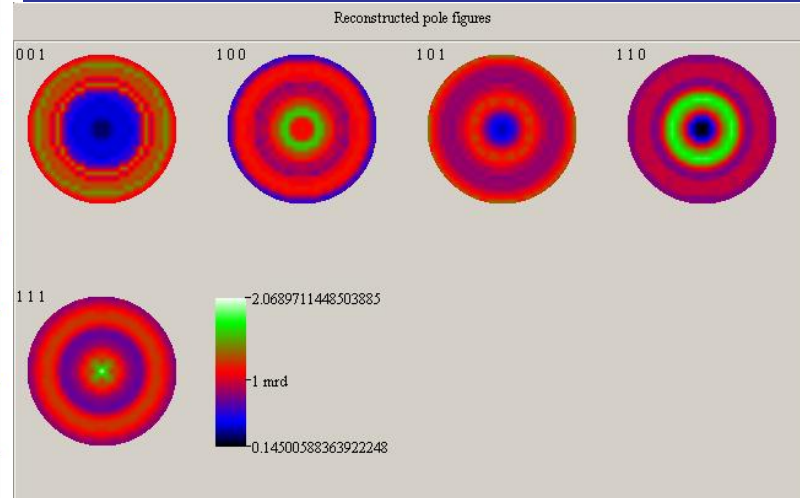
overlapping of reflections from the film and the substrate

TEXTURE effects:
peaks that do not appear at low χ angles

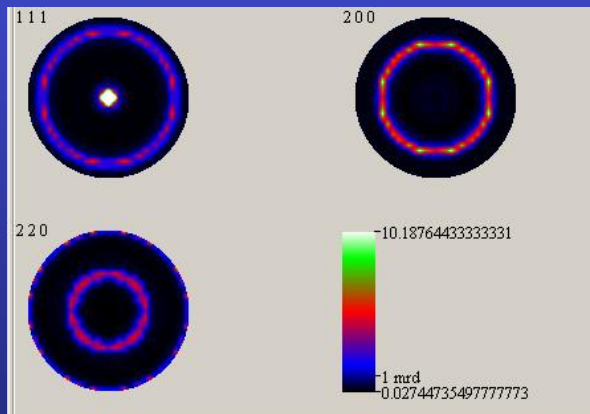




PCT



Pt

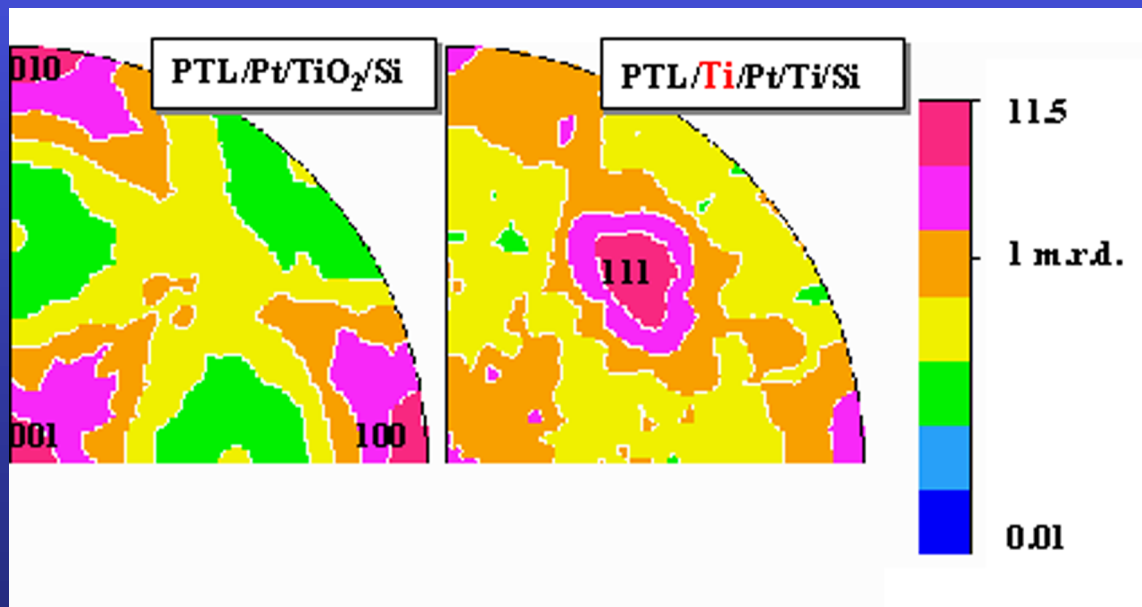


$a = 3.955(1) \text{ \AA}$
 $T = 462(4) \text{ \AA}$
 $t_{\text{iso}} = 458(3) \text{ \AA}$
 $\epsilon' = 0.0032(1) \text{ rms}$

$a = 3.945(1) \text{ \AA}$
 $c = 4.080(1) \text{ \AA}$
 $T = 4080(10) \text{ \AA}$
 $t_{\text{iso}} = 390(7) \text{ \AA}$
 $\epsilon = 0.0067(1) \text{ rms}$

$R_W = 13\%$; $R_B = 12\%$; $R_{\text{exp}} = 22\%$.(Rietveld)
 $R_W = 5\%$; $R_B = 6\%$ (E-WIMV)

Atom	Occupancy	x	y	z
Pb	0.76	0.0	0.0	0.0
Ca	0.24	0.0	0.0	0.0
Ti	1.0	0.5	0.5	0.477(2)
O1	1.0	0.5	0.5	0.060(2)
O2	1.0	0.0	0.5	0.631(1)



Structural parameters

Pt layer

	a (Å)	thickness (nm)	R factors (%)
non-treated substrate			
Pt	3.9108(1)	45.7(3)	$R_W=13, R_B=12, R_{exp}=22$
annealed substrate			
Pt	3.9100(4)	46.4(3)	$R_W=8, R_B=14, R_{exp}=21$
Pt (Recryst. 1h)	3.9114(2)	47.8(3)	$R_W=9, R_B=20, R_{exp}=21$
Pt (Recryst. 2h)	3.9068(1)	46.9(3)	$R_W=9, R_B=14, R_{exp}=22$
Pt (Recryst. 3h)	3.9141(4)	47.5(9)	$R_W=27, R_B=12, R_{exp}=21$

Annealing of the substrate does not introduce significant variations on the structure of the Pt layer

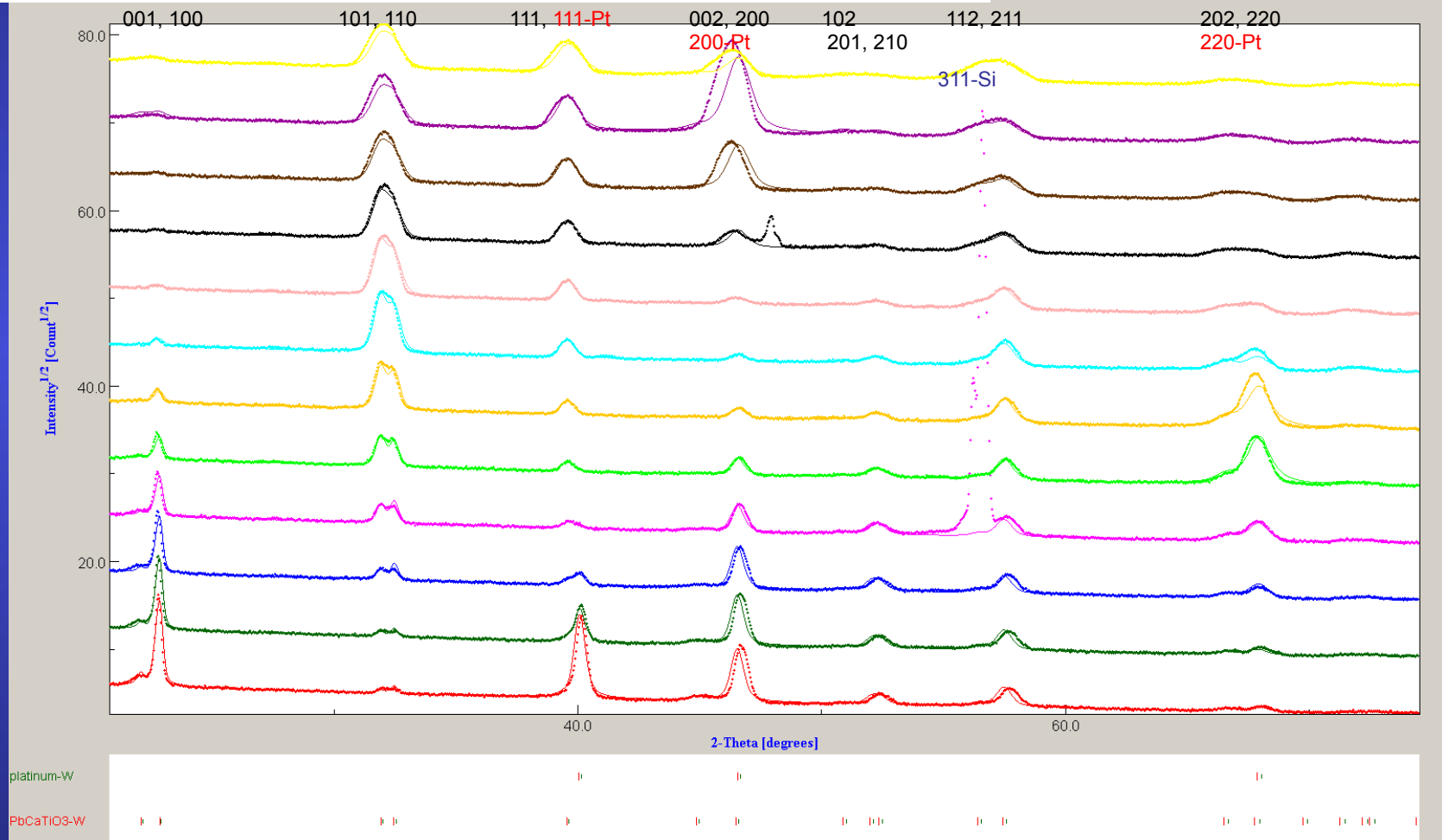
PTC film

	a (Å)	c (Å)	thickness (nm)
on non-treated substrate			
PCT	3.9156(1)	4.0497(6)	272.5(13)
on annealed substrate			
PCT	3.8920(6)	4.0187(8)	279.0(9)
PCT (Recryst. 1h)	3.8929(2)	4.0230(4)	266.1(11)
PCT (Recryst. 2h)	3.8982(2)	4.0227(4)	258.4(9)
PCT (Recryst. 3h)	3.9001(4)	4.0228(11)	253.6(29)

Recrystallisation reduces the stress on the film, and, increases the lattice parameters

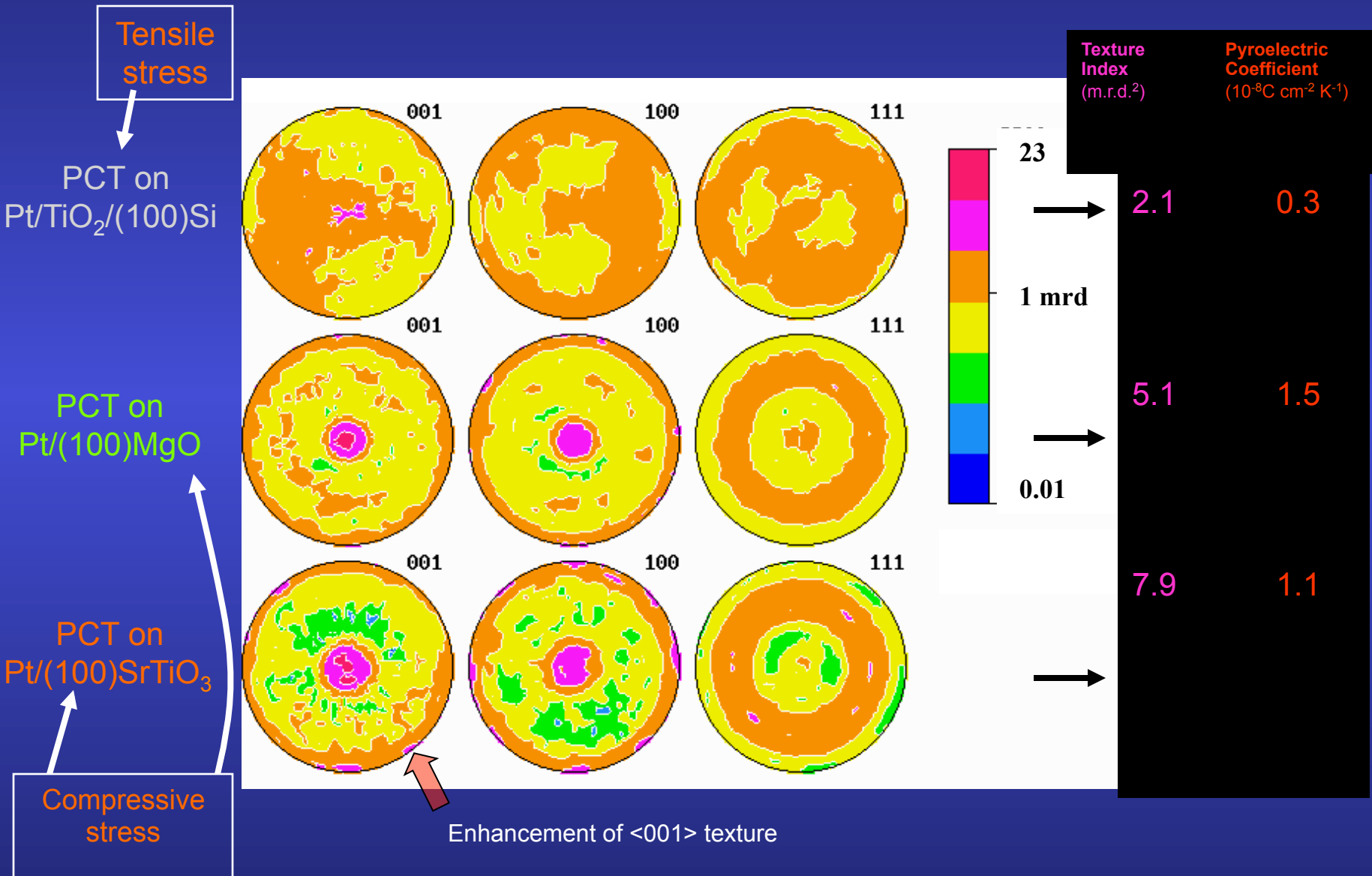
Structural, microstructural and texture quantitative characterisation of ferroelectric thin films by the combined method

Analysis of the X-ray diffraction diagrams of a PCT film on Pt/TiO₂/Si



$R_W = 13\%$; $R_B = 12\%$; $R_{exp} = 22\%$.(Rietveld)
 $R_W = 5\%$; $R_B = 6\%$ (E-WIMV)

Substrate influence on Residual Stress and Texture

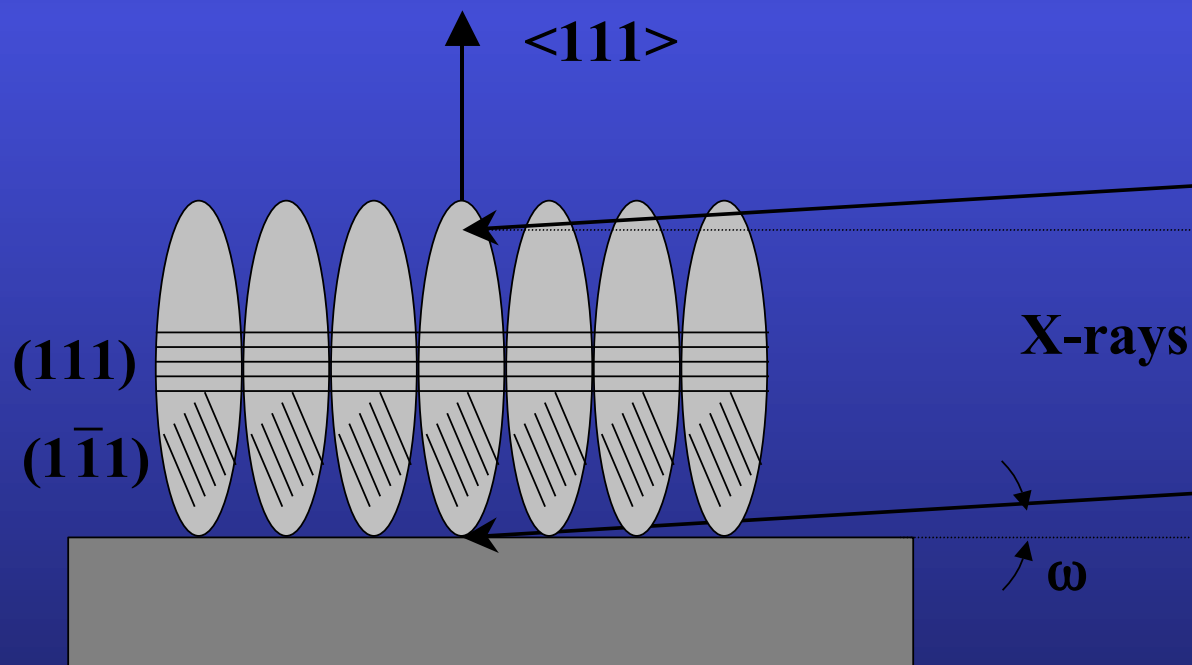
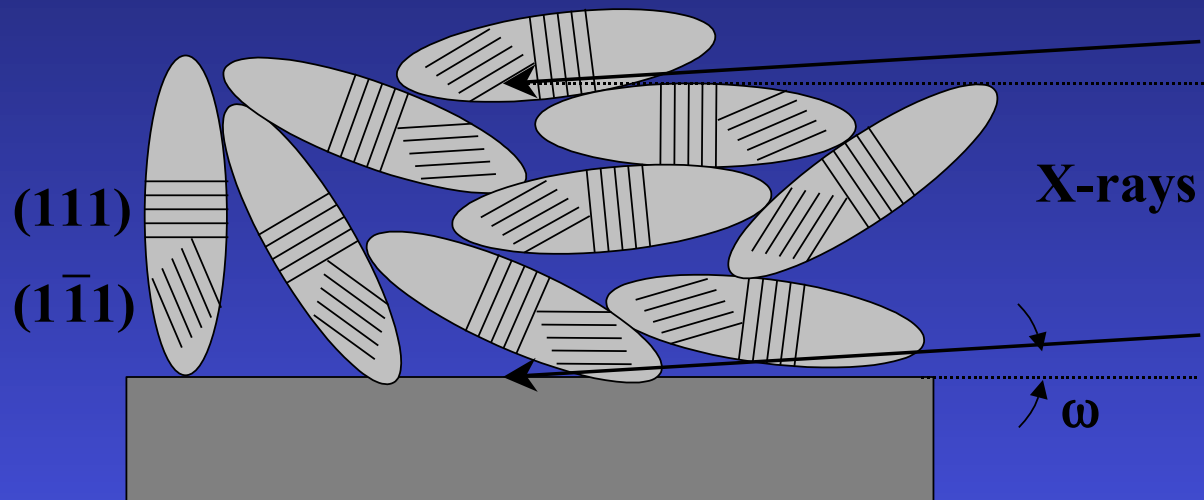


Si nanocrystalline thin films

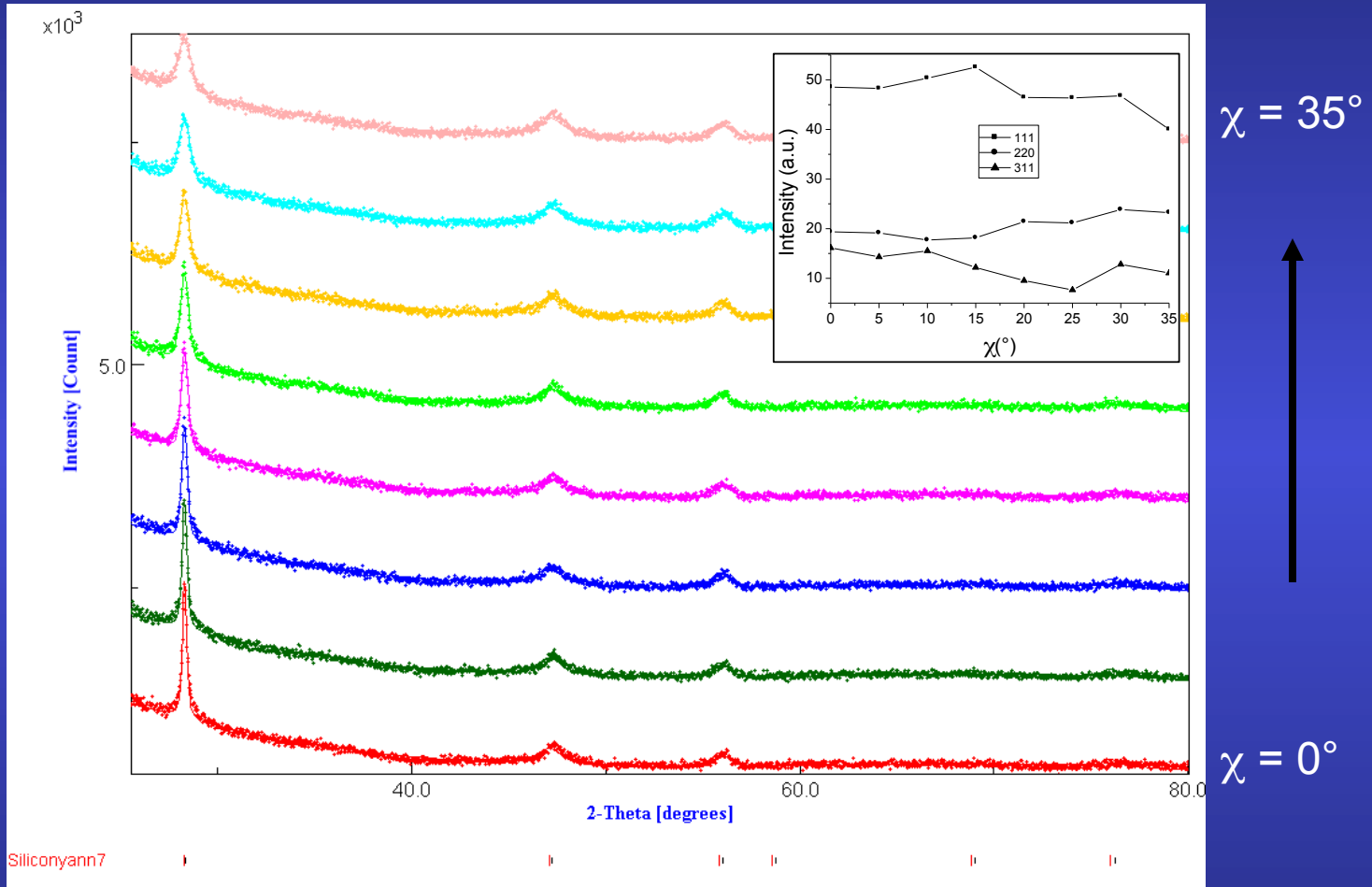
Silicon thin films deposition by reactive magnetron sputtering:

- ⇒ power density $2\text{W}/\text{cm}^2$
- ⇒ total pressure: $p_{\text{total}} = 10^{-1}$ Torr
- ⇒ plasma mixture: H_2 / Ar , $p_{\text{H}_2} / p_{\text{total}} = 80\%$
- ⇒ temperature: 200°C
- ⇒ substrates: amorphous SiO_2 (a- SiO_2)
(100)-Si single-crystals
- ⇒ target-substrate distance (d)
 - a- SiO_2 substrates: $d = 4, 6, 7, 8, 10, 12$ cm
films A, B, C, D, E, F
 - (100)-Si: $d = 6, 12$ cm
films G, H

Aim: quantum confinement, photoluminescence properties



Typical refinement

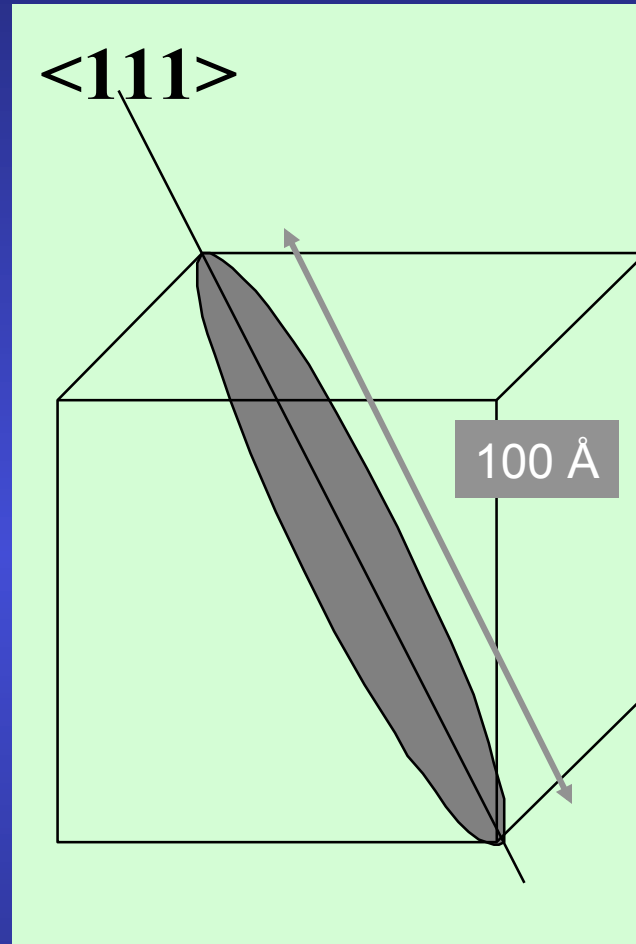


broad, anisotropic diffracted lines, textured samples

Refinement Results

Sample	d (cm)	a (Å)	RX thickness (nm)	Anisotropic sizes (Å)			Texture parameters			Reliability factors (%)			
				<111>	<220>	<311>	Maximum (m.r.d.)	minimum (m.r.d.)	Texture index F ² (m.r.d ²)	RP ₀	R _w	R _B	R _{exp}
A	4	5.4466 (3)	—	94	20	27	1.95	0.4	1.12	1.72	4.0	3.7	3.5
B	6	5.4439 (2)	711 (50)	101	20	22	1.39	0.79	1.01	0.71	4.9	4.3	4.2
C	7	5.4346 (4)	519 (60)	99	40	52	1.72	0.66	1.05	0.78	4.3	4.0	3.9
D	8	5.4461 (2)	1447 (66)	100	22	33	1.57	0.63	1.04	0.90	5.5	4.6	4.5
E	10	5.4462 (2)	1360 (80)	98	20	25	1.22	0.82	1.01	0.56	5.0	3.9	4.0
F	12	5.4452 (3)	1110 (57)	85	22	26	1.59	0.45	1.05	1.08	4.2	3.5	3.7
G	6	5.4387 (3)	1307 (50)	89	22	28	1.84	0.71	1.01	1.57	5.2	4.7	4.2
H	12	5.4434 (2)	1214 (18)	88	22	24	2.77	0.50	1.12	2.97	5.0	4.5	4.3

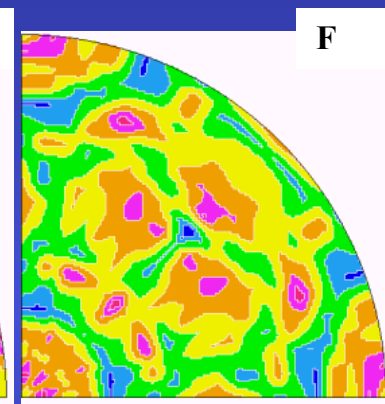
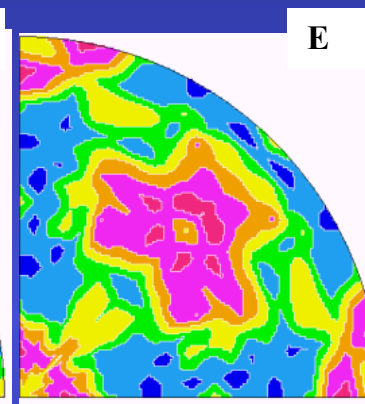
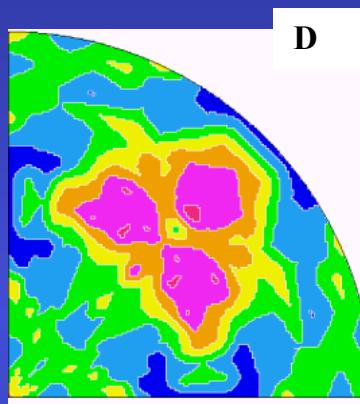
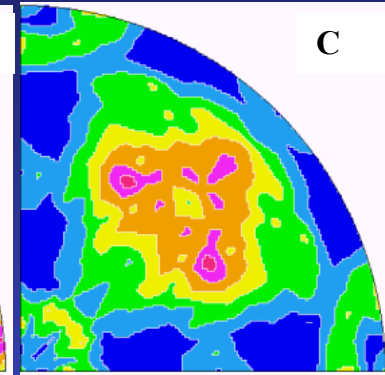
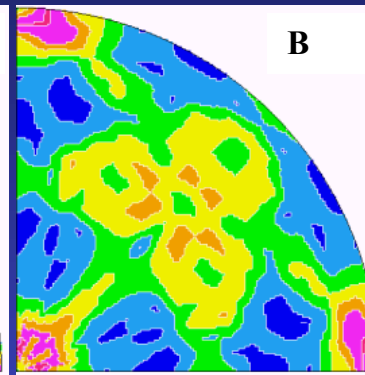
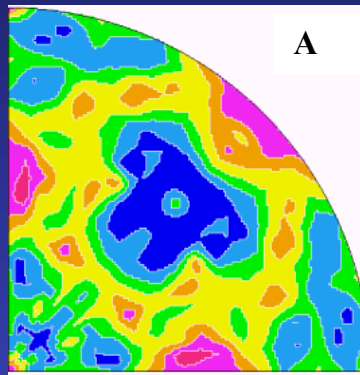
Mean anisotropic shape



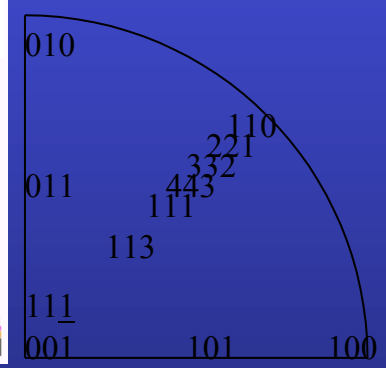
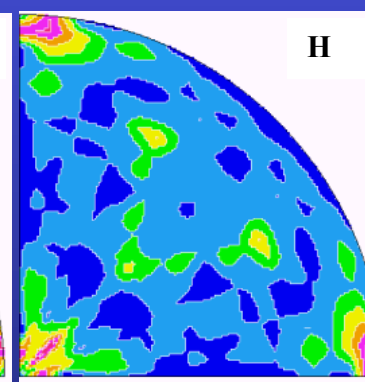
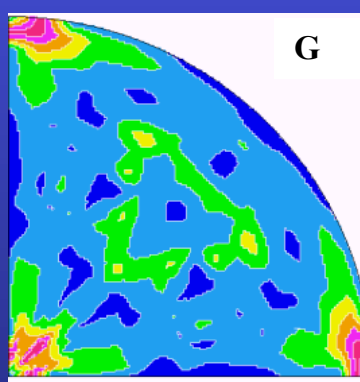
Schematic of the mean crystallite shape for Sample D represented in a cubic cell, as refined using the Popa approach and exhibiting a strong elongation along $\langle 111 \rangle$ (see Table).

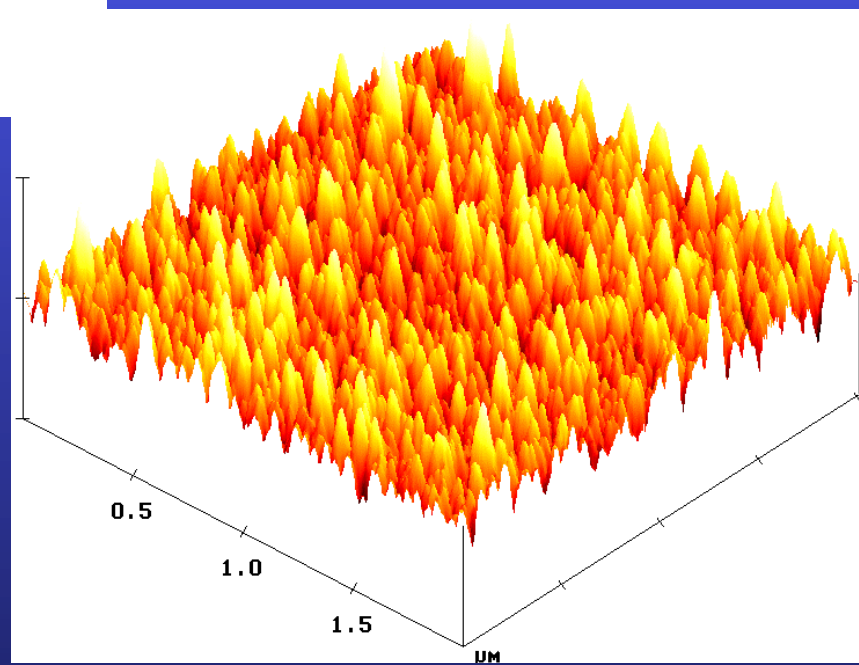
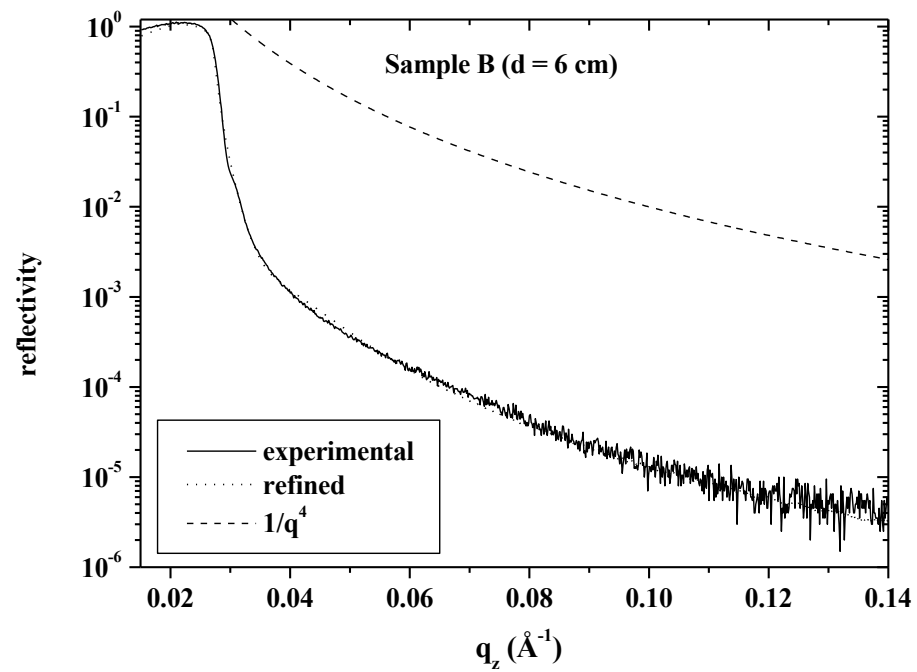
001 Inverse Pole Figures

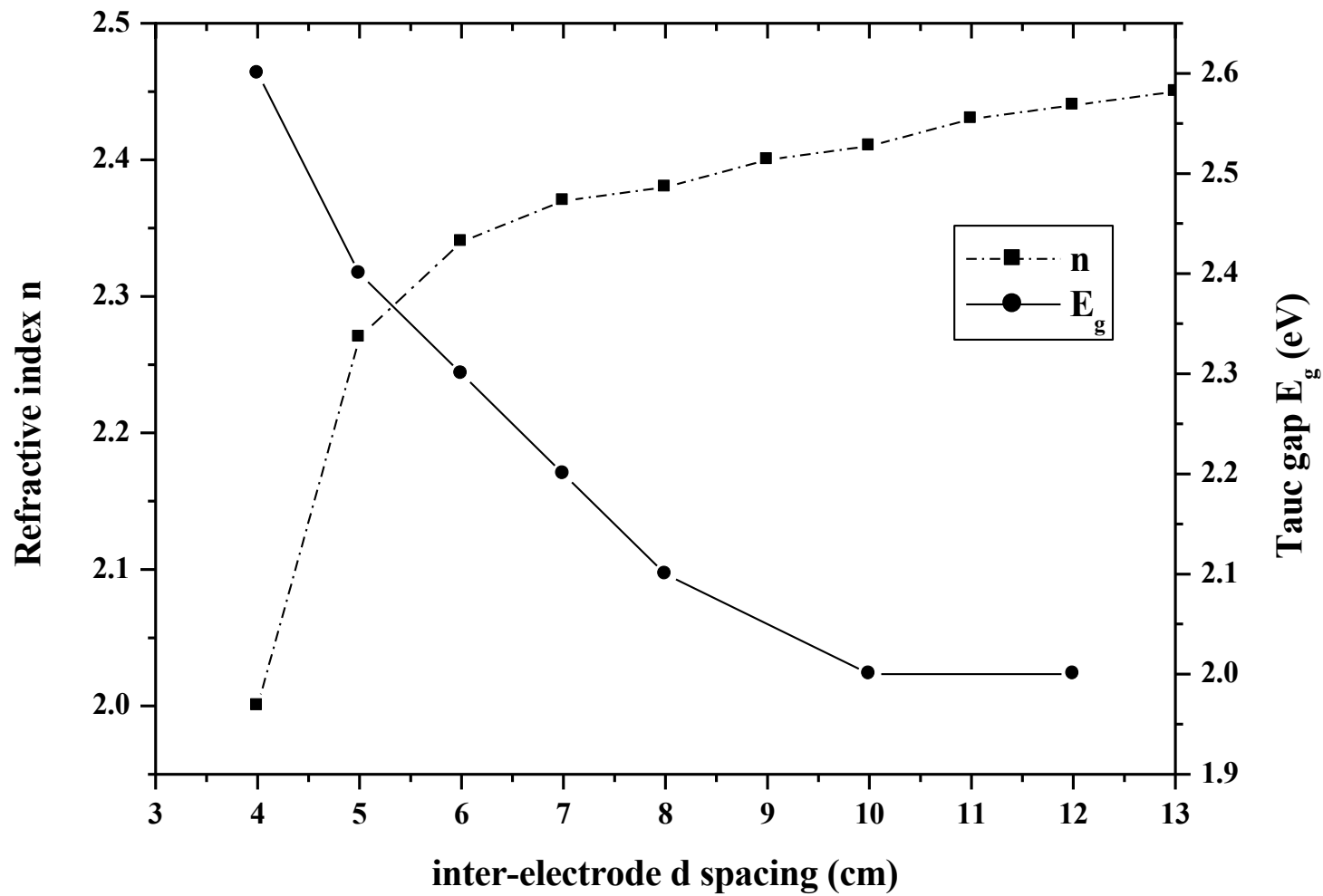
a-SiO₂



(100)-Si







Conclusions

- a) Texture affects phase ratio and structure determination (kept fixed)
- b) Microstructure (crystallite size) affects texture (go to a)
- c) Stresses shift peaks then affects structure and texture determination
- d) Combined analysis may be a solution, unless you can destroy your sample or are not interested in macroscopic anisotropy ...
- e) If you think you can destroy it, perhaps think twice
- f) more information is always needed: local probes ...
- g) www.ensicaen.ismra.fr/~chateign/texture/combined.pdf